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SERIAL NO. U.S. DEPARTMENT OF COMMERCE ATTY. DOCKET NO. Form PTO-1449 Unknown 039153-0450 (G1155) PATENT AND TRADEMARK OFFICE (MODIFIED) APPLICANT Lukanc et al. INFORMATION DISCLOSURE CITATION **GROUP ART UNIT** FILING DATE Unknown Unknown (Use several sheets if necessary) U.S. PATENT DOCUMENTS FILING DATE SUB-**DOCUMENT CLASS EXAMINER** NAME DATE **CLASS** REF **APPROPRIATE** NUMBER INITIAL 01/30/2001 Todd Lukanc 09/772,3277 A4 5 430 05/08/2001 Wang et al. 6,228,539 B1 **A2** 5 430 01/12/1999 Wang et al. 5,858,580 **A3** 5 430 Liebmann et al. 09/15/1998 5,807,649 A4 430 311 11/12/1996 Spence 5,573,890 Α5 FOREIGN PATENT DOCUMENTS TRANSLATION SUB-DOCUMENT **CLASS** COUNTRY DATE CLASS NO YES REF NUMBER OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) Levenson et al., "Improving Resolution in Photolithography with a Phase-Shifting Mask," IEEE Transactions On Electron Devices, Vol. ED-29, No. 12, December 1982, pp. 1828-36. **A6** Lin, B. J., "Phase-Shifting Masks Gain an Edge," Circuits & Devices, March 1993, pp. 28-35. **A7** DATE CONSIDERED **EXAMINER** EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include any copy of this form with next communication to applicant.